

May 3, 2002

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5/23/02

To: Commissioner of Patents and Trademarks
Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572
20 McIntosh Drive
Poughkeepsie, N.Y. 12603

Subject:	Serial No. 10/072,102 02/08/02
	Chew Hoe Ang et al.
	A METHOD TO PATTERN SMALL FEATURES BY USING A RE-FLOWABLE HARD MASK
	Grp. Art Unit: 1752

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TC 1700

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

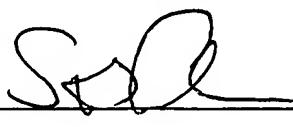
The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56. Copies of each document is included herewith.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner of Patents and
Trademarks, Washington, D.C. 20231, on May 14, 2002.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

 5/14/02

U.S. Patent 4,022,932 to Feng, "Resist Reflow Method for Making Submicron Patterned Resist Masks," describes a resist reflow method for making submicron patterned resist masks.

U.S. Patent 5,899,746 to Mukai, "Method of Forming Pattern," describes a method for making small patterns by eroding a photoresist pattern.

U.S. Patent 4,824,747 to Andrews, "Method of Forming a Variable Width Channel," describes a method for forming a variable width channel.

U.S. Patent 4,449,287 to Maas et al., "Method of Providing a Narrow Groove or Slot in a Substrate Region, in Particular a Semiconductor Substrate Region," describes a method of providing a narrow groove or slot in a substrate region.

U.S. Patent 4,546,066 to Field et al., "Method for Forming Narrow Images on Semiconductor Substrates," describes a method for forming narrow images on semiconductor substrates.

Sincerely,



Stephen B. Ackerman,
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